What is Claimed is:

1. An apparatus for treating gaseous pollutants, comprising:

a gas inlet part, comprising a gas inlet chamber and at least one guide pipe, the at least one guide pipe communicating with the gas inlet chamber and guiding an effluent stream from a semiconductor process to the gas inlet chamber;

a first scrubbing tower, coupled to a bottom end of the gas inlet part, extending vertically and comprising a first top opening communicating with the gas inlet chamber, a first chamber communicating with the first top opening, an inner wall in the first chamber, a liquid inlet laterally communicating with the first chamber, and a first bottom opening communicating with the first chamber, the liquid inlet being configured to allow a water flow entering the first chamber so as to form a water curtain along the inner wall;

a second scrubbing tower, disposed adjacent to the first scrubbing tower, extending vertically and comprising a second bottom opening communicating with the first chamber, a second chamber communicating with the second bottom opening, a second top opening communicating with the second chamber, and a plurality of eductors disposed in the second chamber;

a third scrubbing tower, disposed adjacent to the second scrubbing tower, extending vertically and comprising a third top opening communicating with the second chamber, a third chamber communicating with the third top opening, a third bottom opening

communicating with the third chamber, a flow-guiding device disposed adjacent to the third top opening, and at least one packed bed positioned below the flow-guiding device to receive a gas flow from the flow-guiding device; and

a circulating water tank, coupled to bottom ends of the first scrubbing tower, the second scrubbing tower and the third scrubbing tower, and comprising a water collection space for storing a liquid, a first upper opening, a second upper opening and a third upper opening, the first upper opening, the second upper opening and the third upper opening respectively communicating with the first chamber, the second chamber and the third chamber, and the water collection space comprising a first region, a second region and a barrier disposed between the first region and the second region;

wherein the first region forms, between the first bottom opening of the first scrubbing tower and the second bottom opening of the second scrubbing tower, a first flow channel exposed to the liquid and configured to allow the effluent stream flowing from the first scrubbing tower to the third scrubbing tower through the second scrubbing tower, and the second region receives the effluent stream driven by the flow-guiding device of the third scrubbing tower; and

wherein the flow-guiding device is disposed in an upper compartment of the third chamber, and the upper compartment laterally communicates with the third top opening and downwardly communicates with the at least one packed bed.

2. The apparatus for treating gaseous pollutants according to claim

1, wherein the flow-guiding device comprises a fluid supply tube disposed vertically, a flow-guiding tube positioned below the fluid supply tube, and a lateral gas inlet region positioned between the fluid supply tube and the flow-guiding tube, the flow-guiding tube is aligned with the fluid supply tube to receive an injection fluid from the fluid supply tube, and the injection fluid generates a driving force in the lateral gas inlet region for guiding the gas flow to flow toward and out of an opening of the flow-guiding tube.

3. The apparatus for treating gaseous pollutants according to claim 2, wherein the flow-guiding tube is in the shape of a cone with a narrow top and a wide bottom.

4. The apparatus for treating gaseous pollutants according to claim 1, wherein the flow-guiding device is a non-mechanical flow-guiding device.